

ABSTRACT OF THE DISCLOSURE

A semiconductor processing apparatus capable of diagnosing re-assembly fault of a process chamber after wet cleaning or a condition of the process chamber such as deposition of reaction products and cutoff of components, and a diagnosis method of the semiconductor processing apparatus. A semiconductor processing apparatus for imparting plasma treatment to a sample arranged in a vacuum process chamber includes a plasma generation apparatus for generating plasma inside a vacuum process chamber and a process gas introduction device for introducing a process gas into the vacuum process chamber. The semiconductor processing apparatus includes an oscillator for imparting mechanical oscillation to the semiconductor processing apparatus and a receiver for detecting mechanical oscillation generated by the oscillator in the semiconductor processing apparatus.